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Metal-oxide-semiconductor field effect transistors including a plurality of nanosheets

Abstract

An integrated circuit device includes: a semiconductor on insulator (SOI) substrate layer including a base substrate layer, an insulating substrate layer, and a cover substrate layer; a semiconductor substrate layer; a plurality of first fin-type active areas and a plurality of second fin-type active areas each defined by a plurality of trenches, and extending in a first horizontal direction, in above the SOI substrate layer and the semiconductor substrate layer, respectively; a plurality of nanosheet stacked structures comprising nanosheets extending in parallel with each other and spaced apart from upper surfaces of the plurality of first fin-type active areas and the plurality of second fin-type active areas; a plurality of first source/drain regions extending into the SOI substrate layer; and a plurality of second source/drain regions extending into the semiconductor substrate layer. Lower surfaces of the first and second source/drain regions may not be coplanar with each other.

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Background/Summary

CROSS-REFERENCE TO RELATED APPLICATIONS (1) This U.S. non-provisional patent application is a continuation of and claims priority to U.S. application Ser. No. 17/410,325 filed Aug. 24, 2021, which in turn, claims priority under 35 U.S.C. § 119 to Korean Patent Application No. 10-2020-0183521, filed on Dec. 24, 2020, in the Korean Intellectual Property Office, and the entire contents of each above-identified application are incorporated by reference herein.

BACKGROUND

(1) The inventive concepts relate to integrated circuit devices including multi-gate metal-oxide-semiconductor field effect transistors (MOSFETs).

(2) As the degree of integration in integrated circuit device is increased, sizes thereof are being reduced to extreme dimensions (e.g., extremely small dimensions), and the scaling of integrated circuit devices may be reaching limitations. Accordingly, new methods of manufacturing and using structural changes of the integrated circuit devices are being considered in order to improve the performance of the integrated circuit devices. For example, an integrated circuit device equipped with a transistor having a new structure such as a multi-gate MOSFET has been proposed.

SUMMARY

(3) The inventive concepts provide integrated circuit devices equipped with transistors including multi-gate metal-oxide-semiconductor field effect transistors (MOSFETs) having improved operation characteristics.

(4) To achieve the above technical object, and/or to achieve other technical objects relevant to the present disclosure, the inventive concept provides integrated circuit devices that may include: a first region including a semiconductor on insulator (SOI) substrate layer including a base substrate layer, an insulating substrate layer, and a cover substrate layer, and a second region including a semiconductor substrate layer; a plurality of first fin-type active areas defined by a first plurality of trenches in the first region, the first fin-type active areas protruding from a main surface of the SOI substrate layer and extending in a first horizontal direction; a plurality of second fin-type active areas defined by a second plurality of trenches in the second region, the second fin-type active areas protruding from a main surface of the semiconductor substrate layer and extending in the first horizontal direction; a plurality of nanosheet stacked structures above the plurality of first fin-type active areas and the plurality of second fin-type active areas, each of the plurality of nanosheet stacked structures comprising a plurality of nanosheets extending in parallel with each other and spaced apart from upper surfaces of the plurality of first fin-type active areas and the plurality of second fin-type active areas; a plurality of first source/drain regions between adjacent nanosheet stacked structures in the first region, each of the first source/drain regions extending into the SOI

substrate layer and in contact with the insulating substrate layer and having a lower surface at a first vertical level; and a plurality of second source/drain regions in the second region, each of the plurality of second source/drain regions extending into the semiconductor substrate layer and having a lower surface thereof at a second vertical level that is farther from the main surfaces of the SOI substrate layer and the semiconductor substrate layer than the first vertical level.

(5) The inventive concepts provide an integrated circuit device that may include: a semiconductor on insulator (SOI) substrate layer including a base substrate layer, an insulating substrate layer, and a cover substrate layer in a first region; a semiconductor substrate layer in a second region; a plurality of first fin-type active areas and a plurality of second fin-type active areas defined by a plurality of trenches and extending in a first horizontal direction, on the SOI substrate layer and the semiconductor substrate layer, respectively; a plurality of first nanosheets extending in parallel with each other and spaced apart in a vertical direction from the plurality of first fin-type active areas; a plurality of gate electrodes extending in a second horizontal direction that crosses the first horizontal direction, the plurality of gate electrodes on the plurality of first fin-type active areas and the plurality of second fin-type active areas, first portions of the plurality of gate electrodes between vertically adjacent first nanosheets; a gate dielectric layer between the first nanosheets and the plurality of first fin-type active areas; a plurality of first source/drain regions between horizontally adjacent first nanosheets above the plurality of first fin-type active areas, each of the plurality of first source/drain regions extending into the SOI substrate layer to contact the insulating substrate layer and having a lower surface at a first vertical level above the plurality of first fin-type active areas; and a plurality of second source/drain regions above the plurality of second fin-type active areas, each of the plurality of second source/drain regions extending into the semiconductor substrate layer on the plurality of second fin-type active areas and having a lower surface that is at a second vertical level above the plurality of second fin-type active areas that is higher than the first vertical level.

(6) The inventive concepts provide an integrated circuit device that may include: a semiconductor on insulator (SOI) substrate layer including a base substrate layer, an insulating substrate layer, and a cover substrate layer in a first region; a semiconductor substrate layer in a second region different from the first region; a first impurity region in a portion of the SOI substrate layer having a first impurity type; a second impurity region in a portion of the semiconductor substrate layer having a second impurity type; a plurality of first fin-type active areas and a plurality of second fin-type active areas defined by a plurality of trenches and extending in a first horizontal direction, on the SOI substrate layer and the semiconductor substrate layer, respectively; a plurality of nanosheet stacked structures each comprising a plurality of nanosheets extending in parallel with each other and spaced apart from upper surfaces of the plurality of first fin-type active areas and the plurality of second fin-type active areas; a plurality of first source/drain regions connected to ends of the plurality of nanosheets adjacent to each other on the plurality of first fin-type active areas, the plurality of first source/drain regions extending through the cover substrate layer and into the insulating substrate layer, and including lower surfaces that are at a first vertical level; a plurality of second source/drain regions extending into the semiconductor substrate layer and contacting the second impurity region on the plurality of second fin-type active areas, the plurality of second source/drain regions including lower surfaces that are at a second vertical level that is higher than the first vertical level; a plurality of gate electrodes extending in a second horizontal direction that crosses the first horizontal direction, the plurality of gate electrodes extending on the plurality of first fin-type active areas and the plurality of second fin-type active areas, each of the plurality of gate electrodes including a main gate unit above a respective one of the plurality of nanosheet stacked structures, and a plurality of sub-gate units each underneath a respective nanosheet of the plurality of nanosheets of the respective one of the plurality of nanosheet stacked structures; a gate dielectric layer arranged between the plurality of gate electrodes and the plurality of nanosheets; and in the first region, a plurality of insulating spacers in the first region between the plurality of

first fin-type active areas and the plurality of nanosheets, the plurality of insulating spacers covering first and second ends of each of the plurality of sub-gate units with the gate dielectric layer therebetween.

Description

BRIEF DESCRIPTION OF THE DRAWINGS

(1) Aspects of the present disclosure and examples of embodiments of the inventive concepts will be more clearly understood from the following detailed description taken in conjunction with the accompanying drawings in which:

(2) FIGS. 1-7, 8A, 8B, 9-13, 14A, and 14B are cross-sectional views illustrating a fabrication method of an integrated circuit device, and also illustrate the integrated circuit device fabricated by using the fabrication method, according to some embodiments;

(3) FIGS. 15 through 19 are cross-sectional views of integrated circuit devices, according to some embodiments;

(4) FIGS. 20A and 20B are cross-sectional views of integrated circuit devices, according to some embodiments;

(5) FIG. 21 is a cross-sectional view of an integrated circuit device, according to some embodiments; and

(6) FIGS. 22A, 22B, 23A, and 23B are cross-sectional views illustrating a manufacturing method of an integrated circuit device, and illustrate the integrated circuit device manufactured by using the manufacturing method, according to some embodiments.

DETAILED DESCRIPTION OF THE EMBODIMENTS

(7) FIGS. 1 through 14B are cross-sectional views illustrating a fabrication method of an integrated circuit device, and illustrating an integrated circuit fabricated by using the fabrication method, according to some embodiments. FIGS. 1 through 8A and 9 through 14A are cross-sectional views illustrating Y-Z surfaces, and FIGS. 8B and 14B are cross-sectional views illustrating X-Z surfaces taken along V1-V1' line and V2-V2' line in FIGS. 8A and 14A, respectively.

(8) Referring to FIG. 1, a semiconductor on insulator (SOI) substrate 100 is provided. The SOI substrate 100 may include a base substrate layer 101, an insulating substrate layer 102, and a cover substrate layer 103, which are sequentially stacked, and a first region R1 and a second region R2 are provided.

(9) The base substrate layer 101 may include a semiconductor such as Si and Ge, or a compound semiconductor material such as SiGe, SiC, GaAs, InAs, and InP. In some embodiments, the base substrate layer 101 may include at least one of a Group III-V material and a Group IV material. The Group III-V material may include a binary, ternary, or quaternary compound including at least one Group III element and at least one Group V element. The insulating substrate layer 102 may include an insulating material. The insulating substrate layer 102 may include, for example, a silicon oxide. The insulating substrate layer 102 may have a thickness of several tens of nm. For example, the insulating substrate layer 102 may have a thickness of about 10 nm (nanometers) to about 20 nm. The cover substrate layer 103 may include a semiconductor material such as Si and Ge, or a compound semiconductor material such as SiGe, SiC, GaAs, InAs, and InP. In some embodiments, the cover substrate layer 103 may include a semiconductor material of a different type from the base substrate layer 101. The cover substrate layer 103 may have a thickness of about 10 nm. For example, the base substrate layer 101 may include Si, and the cover substrate layer 103 may include any one of the Group III-V material described above.

(10) Referring to FIG. 2, a substrate recess 100R may be formed by removing both the cover substrate layer 103 and the insulating substrate layer 102 in the second region R2. An upper surface of the base substrate layer 101 may be exposed by the substrate recess 100R. In other words, the

base substrate layer **101** may be exposed by a lower surface of the substrate recess **100R**. In some embodiments, in the process of forming the substrate recess **100R**, an upper portion of the base substrate layer **101** may be removed together with both the cover substrate layer **103** and the insulating substrate layer **102** in the second region **R2**.

(11) The base substrate layer **101**, the insulating substrate layer **102**, and the cover substrate layer **103** sequentially stacked in the first region **R1** may be referred to as an SOI substrate layer **100A**. Accordingly, the SOI substrate layer **100A** may be arranged in the first region **R1**, and the base substrate layer **101** may be arranged in the second region **R2**.

(12) Referring to FIG. 3, in the second region **R2**, an epi-substrate layer **101E** may be formed on the base substrate layer **101** that fills the substrate recess **100R**. The epi-substrate layer **101E** may include a semiconductor material. The epi-substrate layer **101E** may be formed to have an identical crystallization to the base substrate layer **101**, by using an epitaxial growth method using the base substrate layer **101** as a seed. In some embodiments, the epi-substrate layer **101E** may include a semiconductor material of the same type as the base substrate layer **101**. In some embodiments, the epi-substrate layer **101E** may include a semiconductor material of a different type having identical crystallization to the base substrate layer **101**. For example, the base substrate layer **101** may include Si, and the epi-substrate layer **101E** may include GE or SiGe.

(13) In the second region **R2**, the epi-substrate layer **101E** formed on the base substrate layer **101** and the base substrate layer **101** may be referred to as a semiconductor substrate layer **100B**. Accordingly, the SOI substrate layer **100A** may be arranged in the first region **R1**, and the base substrate layer **101B** may be arranged in the second region **R2**. Herein, the SOI substrate layer **100A** and the semiconductor substrate layer **100B** taken together may be referred to as a 'substrate.'

(14) In some embodiments, an upper surface of the SOI substrate layer **100A** may be at the same vertical level as an upper surface of the semiconductor substrate layer **100B** from the upper surface of the base substrate layer **101**. For example, the upper surface of the SOI substrate layer **100A** may be coplanar with the upper surface of the semiconductor substrate layer **100B**.

(15) In some embodiments, a preliminary epi-layer may be formed over the first region **R1** and the second region **R2**. The preliminary epi-layer may fill the substrate recess **100R** and may cover an upper surface of the cover substrate layer **103** and an upper surface of the base substrate layer **101**. Thereafter, the epi-substrate layer **101E** may be formed by performing a planarization operation and removing a portion of an upper surface of the preliminary epi-layer so that the cover substrate layer **103** in the first region **R1** is exposed. In the process of performing the planarization operation for forming the epi-substrate layer **101E**, a portion of the upper surface of the cover substrate layer **103** may be removed together, and in this case, a thickness of the cover substrate layer **103** illustrated in FIG. 3 may be less than that of the cover substrate layer **103** illustrated in FIGS. 1 and 2.

(16) In some embodiments, the preliminary epi-layer may include the same material as the cover substrate layer **103**. After the preliminary epi-layer is formed that fills the substrate recess **100R** and covers the upper surface of the cover substrate layer **103** and the upper surface of the base substrate layer **101** in the second region **R2**, the epi-substrate layer **101E** may be formed by performing the planarization operation and removing a portion of the upper surface of the preliminary epi-layer. In some embodiments, some of the preliminary epi-layer may remain on the cover substrate layer **103**, but because the preliminary epi-layer and the cover substrate layer **103** may include the same material as each other, the preliminary epi-layer and the cover substrate layer **103** may be handled as the cover substrate layer **103**, and in this case, the thickness of the cover substrate layer **103** illustrated in FIG. 3 may be greater than that of the cover substrate layer **103** illustrated in FIGS. 1 and 2.

(17) Referring to FIG. 4, a first impurity region **104** may be formed by injecting an impurity of a first conductivity into a portion of the SOI substrate layer **100A**, and a second impurity region **105**

may be formed by injecting an impurity of a second conductivity into a portion of the semiconductor substrate layer **100B**. For example, when the first region **R1** is an NMOS region, and the second region **R2** is a PMOS region, the impurity of a first conductivity may include a p-type impurity, and the impurity of a second conductivity may include an n-type impurity. The lower surfaces of the first impurity region **104** and the second impurity region **105** may be located at the same vertical level as each other from the base substrate layer **101**, but the present disclosure is not limited thereto. For example, the lower surface of the first impurity region **104** may be at a lower level than the lower surface of the second impurity region **105**, or the lower surface of the first impurity region **104** may be at a higher level than the lower surface of the second impurity region **105**.

(18) In some embodiments, the first impurity region **104** may be formed at a portion of the upper surface of the base substrate layer **101** of the SOI substrate layer **100A**, but the present disclosure is not limited thereto. In some embodiments, the first impurity region **104** may be formed in some of the upper portion of the base substrate layer **101** together with the cover substrate layer **103** of the SOI substrate layer **100A**. In this case, the impurity of the first conductivity may be injected into the insulating substrate layer **102**, but because the insulating substrate layer **102** includes an insulating material, the impurity of the first conductivity may not be applied to the first impurity region **104**.

(19) In some embodiments, the second impurity region **105** may be formed in some of the upper portion of the semiconductor substrate layer **100B**, but the present disclosure is not limited thereto. In some embodiments, the second impurity region **105** may be formed only in some of an upper portion of the semiconductor substrate layer **100B**, but in some embodiments may not be formed in the uppermost portion of the semiconductor substrate layer **100B**.

(20) Referring to FIG. 5, a plurality of sacrificial semiconductor layers **106S** and a plurality of nanosheet semiconductor layers **NS** may be alternately stacked on the substrate in the first region **R1** in which the SOI substrate layer **100A** is arranged and in the second region **R2** in which the semiconductor substrate layer **100B** is arranged. The plurality of sacrificial semiconductor layers **106S** and the plurality of nanosheet semiconductor layers **NS** may include different semiconductor materials from each other. In some embodiments, the plurality of nanosheet semiconductor layers **NS** may include a single material. In some embodiments, the plurality of nanosheet semiconductor layers **NS** may include the same material as a material of at least one of a cover substrate layer **102** of the SOI substrate layer **100A** and the semiconductor substrate layer **100B**. In some embodiments, the plurality of sacrificial semiconductor layers **106S** may include SiGe, and the plurality of nanosheet semiconductor layers **NS** may include Si, but the present disclosure is not limited thereto.

(21) All of the plurality of sacrificial semiconductor layers **106S** may be formed to have an equal thickness as each other, but the present disclosure is not limited thereto. In some embodiments, a thickness of a sacrificial semiconductor layer **106S** closest to the substrate may be greater than thicknesses of the other remaining sacrificial semiconductor layers **106S**.

(22) Referring to FIGS. 5 and 6 together, a plurality of trenches **TRE** may be formed by etching the stacked structure of the plurality of sacrificial semiconductor layers **106S** and the plurality of nanosheet semiconductor layers **NS**, and portions of the SOI substrate layer **100A** and the semiconductor substrate layer **100B**. As a result, a plurality of first fin-type active areas **FAA** and a plurality of second fin-type active areas **FAB** defined by the plurality of trenches **TRE** may be formed in the first region **R1** and the second region **R2**, respectively. The plurality of first fin-type active areas **FAA** may each include a portion of the SOI substrate layer **100A** defined by the plurality of trenches **TRE** in the first region **R1**. The plurality of second fin-type active areas **FAB** may each include a portion of the semiconductor substrate layer **100B** defined by the plurality of trenches **TRE** in the second region **R2**. In the present disclosure, the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB** may be referred to as a plurality of

fin-type active areas.

(23) The plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB may extend in parallel with each other in a first horizontal direction (X direction). The plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB may protrude upward, that is, in a vertical direction (Z direction) from a main surface **100M** of a substrate constituted by the SOI substrate layer **100A** and the semiconductor substrate layer **100B**. The main surface **100M** of the substrate may be the main surface **100M** of the SOI substrate layer **100A** (e.g., base substrate layer **101**) in the first region **R1**, and the main surface **100M** of the semiconductor substrate layer **100B** in the second region **R2**. In the first region **R1**, the plurality of first fin-type active areas FAA may be spaced apart at a constant pitch in a second horizontal direction (Y direction). In the second region **R2**, the plurality of second fin-type active areas FAB may be spaced apart at a constant pitch in the second horizontal direction (Y direction). In some embodiments, the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB may be arranged at an identical pitch in the second horizontal direction (Y direction) in the first region **R1** and the second region **R2**, respectively, but the present disclosure not limited thereto. For example, the plurality of first fin-type active areas FAA may be spaced apart at a constant first pitch in the first region **R1** in the second horizontal direction (Y direction), and the plurality of second fin-type active areas FAB may be spaced apart at a different constant second pitch in the second region **R2** in the second horizontal direction (Y direction).

(24) In each of the first region **R1** and the second region **R2**, a stacked structure NSS including the plurality of sacrificial semiconductor layers **106S** and a plurality of nanosheets **N1**, **N2**, and **N3** may be arranged on the plurality of fin-type active areas, that is, the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB. The stacked structure NSS of the plurality of nanosheets **N1**, **N2**, and **N3** may be formed by removing a portion of the plurality of nanosheet semiconductor layers NS by etching.

(25) Referring to FIG. 7, a preliminary device separating layer may be formed that fills the plurality of trenches TRE, and thereafter a device separating layer **118** may be formed by performing a recess process and removing a certain thickness from an upper portion of the preliminary device separating layer.

(26) The preliminary device separating layer may be formed on side surfaces of the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB, on side walls and an upper surfaces of the stacked structures NSS of the plurality of nanosheets **N1**, **N2**, and **N3**, and on side surfaces and upper surfaces of the SOI substrate layer **100A** and the semiconductor substrate layer **100B**. The recess process may include performing dry etching, wet etching, or an etching process combining dry and wet etching.

(27) The device separating layer **118** may be formed to include an upper surface that is located at the same level as, or located at substantially at a similar vertical level to, the upper surfaces of the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB. In other words, the side wall of the stacked structure NSS of the plurality of nanosheets **N1**, **N2**, and **N3** and the side walls of the plurality of sacrificial semiconductor layers **106S**, which are on the plurality of first fin-type active areas FAA and on the plurality of second fin-type active areas FAB, may be exposed.

(28) Referring to FIGS. 8A and 8B, in the first region **R1** and the second region **R2**, a plurality of dummy gate structures DGS may be formed that cross at least portions of the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB and extending on the stacked structure NSS of the plurality of nanosheets **N1**, **N2**, and **N3**, and the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB. The plurality of dummy gate structures DGS may extend in parallel with each other in the second horizontal direction (Y direction).

(29) The dummy gate structure DGS may have a structure in which an oxide layer **D12**, a dummy

gate layer **D14**, and a capping layer **D16** are sequentially stacked. In an example for forming the dummy gate structure **DGS**, the oxide layer **D12**, the dummy gate layer **D14**, and the capping layer **D16** may be formed and patterned such that only some portions of the oxide layer **D12**, the dummy gate layer **D14**, and the capping layer **D16** remain, such that the oxide layer **D12**, the dummy gate layer **D14**, and the capping layer **D16** cover exposed surfaces of the stacked structure **NSS** and the plurality of sacrificial semiconductor layers **106S** that cover upper portions of the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB**, exposed surfaces of the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB**, and an exposed upper surface of the device separating layer **118**.

(30) In some embodiments, the dummy gate layer **D14** may include a polysilicon layer, and the capping layer **D16** may include a silicon nitride layer, but the present disclosure is not limited thereto.

(31) A gate spacer **130** may be formed to cover both side walls of the dummy gate structure **DGS**. For forming the gate spacer **130**, a spacer layer covering the dummy gate structure **DGS** may be formed, and then the spacer layer may be etched back so that the gate spacer **130** remains. The gate spacer **130** may include, for example, a silicon nitride layer.

(32) Referring to FIG. 9, a plurality of first recess regions **RS1** and a plurality of second recess regions **RS2** may be formed in the first region **R1** and the second region **R2**, respectively, by removing portions of the stacked structure **NSS** of the plurality of nanosheets **N1**, **N2**, and **N3** and the plurality of sacrificial semiconductor layers **106S** by using the dummy gate structure **DGS** and the gate spacer **130** as etching masks.

(33) In some embodiments, in the process of etching portions of the plurality of nanosheets **N1**, **N2**, and **N3** and the plurality of sacrificial semiconductor layers **106S** for forming the plurality of first recess regions **RS1** and the plurality of second recess regions **RS2**, some of the upper portions of the first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB** may also be removed. For example, each of the plurality of first recess regions **RS1** may penetrate the cover substrate layer **103** and may extend into the insulating substrate layer **102**. Each of the plurality of second recess regions **RS2** may extend into the semiconductor substrate layer **100B**.

(34) In some embodiments, each of the plurality of first recess regions **RS1** may extend into the insulating substrate layer **102**, and the insulating substrate layer **102** may be exposed by the first recess regions **RS1**. In some embodiments, each of the plurality of second recess regions **RS2** may extend into the semiconductor substrate layer **100B**, and the second impurity region **105** may be exposed by the plurality of second recess regions **RS2**. A bottom of the first recess region **RS1** may be at a first vertical level **LV1**, and a bottom of the second recess region **RS2** may be at a second vertical level **LV2** that is higher than the first vertical level **LV1**. The second vertical level **LV2** may be farther than the first vertical level **LV1** from the main surface **100M** of the substrate that includes the SOI substrate layer **100A** and the semiconductor substrate layer **100B**.

(35) Referring to FIG. 10, portions of the plurality of sacrificial semiconductor layers **106S** exposed to both sides of each of the plurality of nanosheets **N1**, **N2**, and **N3** in the plurality of first recess regions **RS1** may be removed by using an isotropic etching process in the first region **R1**. Thereafter, insulating spacers **140** may be formed that fill some of the areas between each of the plurality of nanosheets **N1**, **N2** resulting from the isotropic etching process. The insulating spacers **140** may include, for example, silicon nitride layers. In some embodiments, each insulating spacer **140** may be formed by stacking a plurality of insulating layers. In some embodiments, the insulating spacers **140** may be formed only in the first region **R1**, and may not be formed in the second region **R2**.

(36) After the insulating spacers **140** are formed in the first region **R1**, a plurality of first source/drain regions **160A** and a plurality of second source/drain regions **160B** may be formed in the first region **R1** and the second region **R2**, respectively. The plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B** may include a semiconductor

material formed by using an epitaxial growth method using as seeds the exposed side walls of the plurality of nanosheets **N1**, **N2**, and **N3** and the exposed surfaces of the first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB**. For example, the plurality of first source/drain regions **160A** may be formed by using an epitaxial growth method using as seeds the cover substrate layer **103** and the stacked structure **NSS** of the plurality of nanosheets **N1**, **N2**, and **N3**. The plurality of second source/drain regions **160B** may be formed by using an epitaxial growth method using as seeds the semiconductor substrate layer **100B** and the stacked structure **NSS** of the plurality of nanosheets **N1**, **N2**, and **N3**.

(37) In some embodiments, the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B** may include different materials from each other, and each of the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B** may be formed by performing separate epitaxial growth methods. For example, the first source/drain regions **160A** may include Si, but not Ge. In some embodiments, the plurality of first source/drain regions **160A** may include a semiconductor material such as Si, a compound semiconductor material such as SiC, or a multi-layer structure thereof. The second source/drain region **160B** may include Ge. In some embodiments, the second source/drain regions **160B** may include a semiconductor material such as Ge, a compound semiconductor material such as SiGe, a multi-layer structure thereof, or a semiconductor material such as Si, and a multi-layer structure thereof.

(38) The plurality of first source/drain regions **160A** may fill portions of the plurality of first recess regions **RS1**, and each of the plurality of first source/drain regions **160A** may extend into the insulating substrate layer **102**, and a lower surface of each of the plurality of first source/drain regions **160A** may contact the insulating substrate layer **102**. The plurality of second source/drain regions **160B** may fill portions of the plurality of second recess regions **RS2**, each of the plurality of second source/drain regions **160B** may extend into the semiconductor substrate layer **100B**, and a lower surface of each of the plurality of second source/drain regions **160B** may contact the second impurity region **105**. The lower surface of the first source/drain region **160A** may be at the first vertical level **LV1**, and the lower surface of the second source/drain region **160B** may be at the second vertical level **LV2** that is higher than the first vertical level **LV1**, or farther from the main surface **100M**.

(39) Referring to FIGS. **10** and **11**, an inter-gate insulating layer **172** may be formed on the plurality of first source/drain regions **160A**, the plurality of second source/drain regions **160B**, the plurality of dummy gate structures **DGS**, and the plurality of dummy gate structures **DGS**. Thereafter, portions of the inter-gate insulating layer **172** and the capping layer **D16** covering an upper surface of the dummy gate layer **D14** may be removed by planarizing the inter-gate insulating layer **172**, and/or grinding the gate spacer **130** and the inter-gate insulating layer **172** around the capping layer **D16** by a certain thickness from upper portions of the gate spacer **130** and the inter-gate insulating layer **172**. As a result, an upper surface of the inter-gate insulating layer **172** may be at an approximately identical level to the upper surface of the dummy gate layer **D14**. In some embodiments, the inter-gate insulating layer **172** may include silicon oxide layer.

(40) Referring to FIGS. **11** and **12**, a plurality of gate spaces **GS** may be formed, by removing the dummy gate layer **D14** and the oxide layer **D12** thereunder from between the inter-gate insulating layer **172** and the gate spacer **130**, and by removing at least some of the plurality of sacrificial semiconductor layers **106S** remaining in the first region **R1** and the second region **R2**. A portion of each of the surfaces of the plurality of nanosheets **N1**, **N2**, and **N3**, the upper surfaces of the plurality of first fin-type active areas **FAA**, and the upper surfaces of the plurality of second fin-type active areas **FAB** may be exposed via the gate spaces **GS**. In some embodiments, some portions of the plurality of sacrificial semiconductor layers **106S** may not be removed and instead remain.

(41) Referring to FIGS. **12** and **13**, a gate dielectric layer **145** may be formed on surfaces exposed by the plurality of gate spaces **GS**, and a plurality of gate electrodes **150** may be formed on the gate

dielectric layer **145** that fill the plurality of gate spaces GS. The plurality of gate electrodes **150** may extend in parallel with each other in the second horizontal direction (Y direction).

(42) In some embodiments, the gate dielectric layer **145** may have a stacked structure of an interfacial layer and a high-k dielectric layer. In some embodiments, the interface layer may include a low dielectric material layer having a dielectric constant of about 9 or less, such as a silicon oxide layer, a silicon oxynitride film, or a combination thereof, as non-limiting examples. In some embodiments, the interface layer may be omitted. The high-k dielectric layer may include a material having a dielectric constant greater than that of the silicon oxide layer. For example, the high-k dielectric layer may have a dielectric constant of about 10 to about 25.

(43) In some embodiments, the gate dielectric layer **145** may include a ferroelectric material layer having a ferroelectric characteristic, and a paraelectric material layer having a paraelectric characteristic. The ferroelectric material layer may have a negative capacitance, and the paraelectric material layer may have a positive capacitance. For example, when two or more capacitors are connected in series, and each of capacitances of the capacitors has a positive value, the total capacitance may be decreased from each of capacitances of individual capacitors. However, when the capacitance of at least one of the two or more capacitors connected to each other in series has a negative value, the total capacitance may be positive and greater than an absolute value of each of individual capacitances.

(44) When the ferroelectric material layer having a negative capacitance and a paraelectric material layer having a positive capacitance are connected to each other in series, the total capacitance value of the ferroelectric material layer and the paraelectric material layer connected to each other in series may be increased. Because the total capacitance value may be increased, a transistor including the ferroelectric material layer may have a subthreshold swing (SS) less than about 60 mV/decade at room temperature.

(45) The ferroelectric material layer may have a ferroelectric characteristic. The ferroelectric material layer may include at least one of hafnium oxide, hafnium zirconium oxide, barium strontium titanium oxide, barium titanium oxide, and lead zirconium titanium oxide. In some embodiments, for example, the hafnium zirconium oxide may include hafnium oxide with zirconium (Zr) doped thereon. As another example, the hafnium zirconium oxide may be a compound of hafnium (Hf), zirconium (Zr), and oxygen (O).

(46) The ferroelectric material layer may further include doped dopant. As non-limiting examples, the dopant may include at least one of aluminum (Al), titanium (Ti), niobium (Nb), lanthanum (La), yttrium (Y), magnesium (Mg), silicon (Si), calcium (Ca), cerium (Ce), dysprosium (Dy), erbium (Er), gadolinium (Gd), germanium (Ge), scandium (Sc), strontium (Sr), and/or tin (Sn). Depending on which ferroelectric material is included in the ferroelectric material layer, a type of the dopant included in the ferroelectric material layer may vary.

(47) When the ferroelectric material layer includes a hafnium oxide, the dopant included in the ferroelectric material layer may include at least one of, as non-limiting examples, gadolinium (Gd), silicon (Si), zirconium (Zr), aluminum (Al), and/or yttrium (Y).

(48) When the dopant is Al, the ferroelectric material layer may include aluminum of about 3 to about 8 at %. For example, a ratio of the dopant may be a ratio of aluminum over a sum of hafnium and aluminum.

(49) When the dopant is Si, the ferroelectric material layer may include silicon of about 2 to 10 at %. When the dopant is Y, the ferroelectric material layer may include yttrium of about 2 to 10 at %. When the dopant is Gd, the ferroelectric material layer may include gadolinium of about 1 to 7 at %. When the dopant is Zr, the ferroelectric material layer may include zirconium of about 50 to 80 at %.

(50) The paraelectric material layer may have a paraelectric characteristic. The paraelectric material layer may include at least one of silicon oxide and a metal oxide of a high-k. The metal oxide included in the paraelectric material layer may include at least one of hafnium oxide, zirconium

oxide, and aluminum oxide, but the present disclosure is not limited thereto.

(51) The ferroelectric material layer and the paraelectric material layer may include the same material as each other. The ferroelectric material layer may not have a paraelectric characteristic, and the paraelectric material layer may not have a ferroelectric characteristic. For example, when the ferroelectric material layer and the paraelectric material layer include hafnium oxide, a crystal structure of the hafnium oxide included in the ferroelectric material layer may be different from that of the hafnium oxide included in the paraelectric material layer.

(52) The ferroelectric material layer may have a thickness having a ferroelectric characteristic. The thickness of the ferroelectric material layer may be, for example, about 0.5 nm to about 10 nm, but the present disclosure is not limited thereto. Because a critical thickness of the ferroelectric material showing a ferroelectric characteristic may vary, the thickness of the ferroelectric material layer may vary depending on the selected ferroelectric material.

(53) As an example, the gate dielectric layer **145** may include one ferroelectric material layer. As another example, the gate dielectric layer **145** may include a plurality of ferroelectric material layers spaced apart from each other. The gate dielectric layer **145** may have a stacked layer structure in which the plurality of ferroelectric material layers and the plurality of paraelectric material layers are stacked alternately.

(54) The gate electrode **150** may include a work function control metal-including layer and a gap-fill metal-including layer that fills an upper space of the work function control metal-including layer. In some embodiments, the gate electrode **150** may have a structure in which a metal nitride layer, a metal layer, a conductive capping layer, and a gap-fill metal layer are sequentially stacked.

(55) The gate electrode **150** may include a main gate unit **150M** that covers the upper surface of the nanosheet stacked structure **NSS** including the plurality of nanosheets **N1**, **N2**, and **N3**, and a plurality of sub-gate units **150S** that are connected to the main gate unit **150M** and formed in a space between each of the plurality of nanosheets **N1**, **N2**, and **N3** and the first fin-type active area **FAA**, and a space between each of the plurality of nanosheets **N1**, **N2**, and **N3** and the second fin-type active area **FAB**. For example, the sub-gate units **150S** may be formed under each of the plurality of nanosheets **N1**, **N2**, and **N3**.

(56) In the first region **R1**, the plurality of insulating spacers **140** may be arranged with the gate dielectric layer **145** therebetween on both ends of each of the plurality of sub-gate units **150S**. In the second region **R2**, the plurality of second source/drain regions **160B** may be arranged with the gate dielectric layer **145** therebetween on both ends of each of the plurality of sub-gate units **150S**. In the first region **R1**, the gate dielectric layer **145** and the insulating spacer **140** may be arranged between the sub-gate unit **150S** and the first source/drain region **160A**. In the second region **R2**, the gate dielectric layer **145** may be present, but the insulating spacer **140** may be absent from between the sub-gate unit **150S** and the second source/drain region **160B**. Accordingly, in the second region **R2**, the sub-gate unit **150S** and the second source/drain region **160B** may directly contact the gate dielectric layer **145** that is arranged therebetween.

(57) Referring to FIGS. **14A** and **14B**, an inter-layer insulating layer **174** that covers the plurality of gate electrodes **150** and the inter-gate insulating layer **172** may be formed, and thereafter a first contact hole **192H** that exposes the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B** may be formed by etching some of the inter-layer insulating layer **174** and the inter-gate insulating layer **172**. A metal silicide layer **162** may be formed on surfaces of the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B** that are exposed via a plurality of first contact holes **192H**. In addition, by etching a portion of the inter-layer insulating layer **174**, a plurality of second contact holes **194H** may be formed that expose upper surfaces of the plurality of gate electrodes **150**, that is, an upper surface of the main gate unit **150M**. In some embodiments, the plurality of first contact holes **192H** and the plurality of second contact holes **194H** may be formed together in a single etching process, but the present disclosure is not limited thereto, and each of the plurality of first contact holes **192H** and

the plurality of second contact holes **194H** may be formed by separate etching processes.

(58) Thereafter, a plurality of first contact plugs **192** may be formed that fill the plurality of first contact holes **192H** and a plurality of second contact plugs **194** may be formed that fill the plurality of second contact holes **194H**, and as a result the integrated circuit device **1** may be formed.

(59) The plurality of first contact plugs **192** may be connected to the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B** via the metal silicide layer **162**, and the plurality of second contact plugs **194** may be connected to the plurality of gate electrodes **150**. In some embodiments, the plurality of first contact plugs **192** and the plurality of second contact plugs **194** may be formed together, but the present disclosure is not limited thereto, and each of the plurality of first contact plugs **192** and the plurality of second contact plugs **194** may be formed in separate processes.

(60) The integrated circuit device **1** may include the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB** that protrude upward in the vertical direction (**Z** direction) from the main surface **100M** of the substrate including the SOI substrate layer **100A** and the semiconductor substrate layer **100B**, and may also include the plurality of nanosheet stacked structures **NSS** that the upper surfaces of the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB** from a location spaced apart in the vertical direction (**Z** direction) from the upper surfaces of the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB**. The plurality of first fin-type active areas **FAA** may protrude upward in the vertical direction (**Z** direction) from the main surface **100M** of the SOI substrate layer **100A** in the first region **R1**, and the plurality of second fin-type active areas **FAB** may protrude upward in the vertical direction (**Z** direction) from the main surface **100M** of the semiconductor substrate layer **100B** in the second region **R2**.

(61) The plurality of trenches **TRE** may limit or define the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB** on the substrate including the SOI substrate layer **100A** and the semiconductor substrate layer **100B**. Side walls of the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB** may be covered by a device separating layer **118** that fills the plurality of trenches **TRE**. Levels of surfaces of the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB** may be from the main surface **100M** at the same level as or at a similar level as a level of an upper surface of the device separating layer **118**.

(62) The plurality of nanosheet stacked structures **NSS** may be spaced apart from the upper surfaces of the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB**. The plurality of nanosheet stacked structures **NSS** may include the plurality of nanosheets **N1**, **N2**, and **N3** that extend in parallel with the upper surfaces of the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB** on the substrate including the SOI substrate layer **100A** and the semiconductor substrate layer **100B**.

(63) The plurality of nanosheets **N1**, **N2**, and **N3** of one nanosheet stacked structure **NSS** may be sequentially stacked one-by-one on the upper surfaces of the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB**. In some embodiments, one nanosheet stacked structure **NSS** includes three nanosheets **N1**, **N2**, and **N3** as illustrated, but the present disclosure is not limited thereto. Each of the plurality of nanosheets **N1**, **N2**, and **N3** may each have a channel region. In some embodiments, the plurality of nanosheets **N1**, **N2**, and **N3** may include a single material.

(64) The plurality of gate electrodes **150** may extend in the second horizontal direction (**Y** direction) that crosses the first horizontal direction (**X** direction), and may extend on the plurality of first fin-type active areas **FAA** and the plurality of second fin-type active areas **FAB**. At least a portion of the plurality of gate electrodes **150** may overlap each of the plurality of nanosheet stacked structures **NSS** in the vertical direction (**Z** direction).

(65) Each of the plurality of gate electrodes **150** may cover the nanosheet stacked structure **NSS**,

and surround at least a portion of the plurality of nanosheet stacked structures NSS. The gate electrode **150** may include the main gate unit **150M** that covers the upper surface of the nanosheet stacked structure NSS, and the plurality of sub-gate units **150S** connected to the main gate unit **150M** and formed in spaces between the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB and each of the plurality of nanosheets N1, N2, and N3, that is, under each of the plurality of nanosheets N1, N2, and N3. The gate dielectric layer **145** may separate the nanosheet stacked structure NSS and the gate electrode **150**.

(66) In the first region R1, the plurality of first source/drain regions **160A** may be formed on the plurality of first fin-type active areas FAA, and in the second region R2, the plurality of second source/drain regions **160B** may be formed on the plurality of second fin-type active areas FAB. Each of the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B** may be connected to adjacent ends of the plurality of nanosheets N1, N2, and N3. In the first region R1, each of the plurality of first source/drain regions **160A** may extend into the SOI substrate layer **100A**. In some embodiments, in the first region R1, each of the plurality of first source/drain regions **160A** may penetrate the cover substrate layer **103**, and extend into the insulating substrate layer **102**, and the lower surface of each of the plurality of first source/drain regions **160A** may contact the insulating substrate layer **102**. In the first region R1, each of the plurality of first source/drain regions **160A** may not contact the first impurity region **104**. In the second region R2, each of the plurality of second source/drain regions **160B** may extend into the semiconductor substrate layer **100B**, and the lower surface of each of the plurality of second source/drain regions **160B** may contact the second impurity region **105**. The lower surface of the first source/drain region **160A** may be at the first vertical level LV1, and the lower surface of the second source/drain region **160B** may be at the second vertical level LV2 that is higher than the first vertical level LV1 and farther from the main surface **100M**.

(67) The integrated circuit device **1** may include a plurality of first transistors TRA equipped in the first region R1, and a plurality of second transistors TRB equipped in the second region R2. Each of the first transistor TRA and the second transistor TRB may be or may include a multi-gate metal-oxide-semiconductor field effect transistor (MOSFET). In some embodiments, the first transistor TRA equipped in the first region R1 may include a multi-gate nMOSFET, and the second transistor TRB equipped in the second region R2 may include a multi-gate pMOSFET.

(68) In some embodiments, when the gate dielectric layer **145** includes the ferroelectric material layer having a ferroelectric characteristic and the paraelectric material layer having a paraelectric characteristic, each of the first transistor TRA and the second transistor TRB may include a negative capacitance (NC) FET using a negative capacitor.

(69) The gate spacer **130** sequentially covering side walls of the gate electrode **150** may be formed on the plurality of nanosheet stacked structures NSS, the plurality of first fin-type active areas FAA, and the plurality of second fin-type active areas FAB. The gate spacer **130** may include a silicon nitride layer, but the present disclosure is not limited thereto. The gate spacer **130** may cover side walls of the main gate unit **150M** of the gate electrode **150**.

(70) In the first region R1, the insulating spacer **140** may contact the first source/drain region **160A** and may be formed in a space between each of the plurality of nanosheets N1, N2, and N3. The insulating spacer **140** may be arranged between the sub-gate unit **150S** and the first source/drain region **160A** in a space between each of the plurality of first fin-type active areas FAA and the plurality of nanosheets N1, N2, and N3. In the second region R2, the insulating spacer **140** may not be formed, and the second source/drain region **160B** may contact the gate dielectric layer **145**.

(71) The inter-gate insulating layer **172** and the inter-layer insulating layer **174** may be sequentially formed on the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B**. Each of the inter-gate insulating layer **172** and the inter-layer insulating layer **174** may include a silicon oxide layer, but the present disclosure is not limited thereto.

(72) The plurality of first contact plugs **192** may be connected to the plurality of first source/drain

regions **160A** and the plurality of second source/drain regions **160B**. The plurality of first contact plugs **192** may penetrate the inter-layer insulating layer **174** and the inter-gate insulating layer **172**, and may be connected to the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B**. The metal silicide layer **162** may be arranged between the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B**, and the first contact plug **192**. In some embodiments, the metal silicide layer **162** may be omitted.

(73) The plurality of second contact plugs **194** may be connected to the plurality of gate electrodes **150**. The second contact plug **194** may penetrate the inter-layer insulating layer **174**, and may be connected to the gate electrode **150**.

(74) Each of the first contact plug **192** and the second contact plug **194** may include metal, conductive metal nitride, or a combination thereof.

(75) In the integrated circuit device **1** according to the inventive concepts, each of the plurality of first transistors TRA formed in the first region R1 may be formed on the SOI substrate layer **100A** including the base substrate layer **101**, the insulating substrate layer **102**, and the cover substrate layer **103**, which are sequentially stacked, and each of the plurality of second transistors TRB formed in the second region R2 may be formed on the semiconductor substrate layer **100B**.

(76) Because the first transistor TRA is separated from the first impurity region **104** by the insulating substrate layer **102**, an off-state leakage current of the first transistor TRA may not occur in the first transistor TRA. Accordingly, because the off-state leakage current of the plurality of first transistors TRA is at least reduced, an operation characteristic of the integrated circuit device **1** according to the inventive concepts may be improved. An on-state current of the first transistor TRA may be formed by using not only the stacked structure of the plurality of nanosheets N1, N2, and N3, but also the cover substrate layer **103** separated from the first impurity region **104** by the insulating substrate layer **102**. Accordingly, because the on-state current of the plurality of first transistors TRA is increased, output characteristics of the integrated circuit device **1** according to the inventive concepts may be improved.

(77) In addition, in the second region R2, the plurality of second source/drain regions **160B** of the plurality of second transistors TRB are formed by using an epitaxial growth method using as seeds the semiconductor substrate layer **100B** in which the second impurity region **105** is formed and also the nanosheet stacked structure NSS of the plurality of nanosheets N1, N2, and N3, and thus, the plurality of second source/drain regions **160B** may have good crystallization. Accordingly, operation characteristics of the plurality of second transistors TRB may be improved.

(78) Therefore, the integrated circuit device **1** according to the inventive concepts may include the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB, in which the operation characteristics are improved, and thus, may secure reliability and the improved operation characteristics.

(79) FIGS. **15** through **19** are cross-sectional views of integrated circuit devices, according to some embodiments. Duplicate descriptions given with reference to FIGS. **1** through **14B** are omitted from descriptions of FIGS. **15** through **19**. FIGS. **15** through **19** are cross-sectional views illustrating X-Z surfaces.

(80) Referring to FIG. **15**, an integrated circuit device **1a** may include the plurality of first transistors TRA equipped in the first region R1, and the plurality of second transistors TRB equipped in the second region R2. Each of the first transistor TRA and the second transistor TRB may include a multi-gate MOSFET.

(81) The integrated circuit device **1a** may include the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB that protrude upward in the vertical direction (Z direction) from the main surface **100M** of the substrate including the SOI substrate layer **100A** and the semiconductor substrate layer **100B**, and the plurality of nanosheet stacked structures NSS that face the upper surfaces of the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB from locations spaced apart from the plurality of first fin-type

active areas FAA and the plurality of second fin-type active areas FAB.

(82) The plurality of nanosheet stacked structures NSS may be spaced apart from the upper surfaces of the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB. The plurality of nanosheet stacked structures NSS may include the plurality of nanosheets N1, N2, and N3 that extend in parallel with the upper surfaces of the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB on the substrate including the SOI substrate layer **100A** and the semiconductor substrate layer **100B**.

(83) The plurality of gate electrodes **150** may extend in the second horizontal direction (Y direction) that cross the first horizontal direction (X direction), and may extend on the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB. The gate electrode **150** may include the main gate unit **150M** that covers the upper surface of the nanosheet stacked structure NSS, and the plurality of sub-gate units **150S** that are connected to the main gate unit **150M** and formed in spaces between the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB and the plurality of nanosheets N1, N2, and N3, that is, under each of the plurality of nanosheets N1, N2, and N3. The gate dielectric layer **145** may separate the nanosheet stacked structure NSS and the gate electrode **150**.

(84) In the first region R1, the plurality of first source/drain regions **160A** may be formed on the plurality of first fin-type active areas FAA, and in the second region R2, the plurality of second source/drain regions **160B** may be formed on the plurality of second fin-type active areas FAB.

(85) The integrated circuit device **1a** may include an air gap AG arranged between each of the plurality of first source/drain regions **160A** and the insulating substrate layer **102**. In FIG. **15**, the air gap AG is illustrated to be arranged at the lower surface of the first recess region RS1, but this is only exemplary, and the present disclosure is not limited thereto. For example, the air gap AG may be arranged between each of the plurality of first source/drain regions **160A** and the insulating substrate layer **102** across the lower surface and lower side walls of the first recess region RS1. Because the air gap AG reduces parasite capacitance, the operation characteristic of the integrated circuit device **1a** may be improved.

(86) The gate spacer **130** sequentially covering side walls of the gate electrode **150** may be formed on the plurality of nanosheet stacked structures NSS, the plurality of first fin-type active areas FAA, and the plurality of second fin-type active areas FAB.

(87) In the first region R1, the insulating spacer **140** that contacts the first source/drain region **160A** may be formed in the space between each of the plurality of nanosheets N1, N2, and N3. In the second region R2, the insulating spacer **140** may not be formed, and the second source/drain region **160B** may contact (e.g., directly contact) the gate dielectric layer **145**.

(88) The inter-gate insulating layer **172** and the inter-layer insulating layer **174** may be sequentially formed on the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B**. The plurality of first contact plugs **192** may be connected to the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B**. The plurality of first contact plugs **192** may penetrate the inter-layer insulating layer **174** and the inter-gate insulating layer **172**, and may be connected to the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B**. The metal silicide layer **162** may be arranged between the plurality of first source/drain regions **160A** and the plurality of second source/drain regions **160B**, and the first contact plug **192**.

(89) The plurality of second contact plugs **194** may be connected to the plurality of gate electrodes **150**, as illustrated in FIG. **14A**.

(90) Referring to FIG. **16**, an integrated circuit device **1b** may include the plurality of first transistors TRAA equipped in the first region R1, and the plurality of second transistors TRB equipped in the second region R2. Each of the first transistor TRAA and the second transistor TRB may include the multi-gate MOSFET.

(91) The integrated circuit device **1b** may include the plurality of first fin-type active areas FAA

and the plurality of second fin-type active areas FAB that protrude upward in the vertical direction (Z direction) from the main surface **100M** of the substrate including the SOI substrate layer **100A** and the semiconductor substrate layer **100B**, and the plurality of nanosheet stacked structures NSS that face the upper surfaces of the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB from locations spaced apart from the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB.

(92) The plurality of nanosheet stacked structures NSS may be apart from the upper surfaces of the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB. The plurality of nanosheet stacked structures NSS may include the plurality of nanosheets **N1**, **N2**, and **N3** that extend in parallel with the upper surfaces of the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB on the substrate including the SOI substrate layer **100A** and the semiconductor substrate layer **100B**.

(93) The plurality of gate electrodes **150** may extend in the second horizontal direction (Y direction) that cross the first horizontal direction (X direction), and may extend on the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB. The gate electrode **150** may include the main gate unit **150M** that covers the upper surface of the nanosheet stacked structure NSS, and the plurality of sub-gate units **150S** that are connected to the main gate unit **150M** and formed in spaces between the plurality of first fin-type active areas FAA and the plurality of second fin-type active areas FAB and the plurality of nanosheets **N1**, **N2**, and **N3**, that is, under each of the plurality of nanosheets **N1**, **N2**, and **N3**. The gate dielectric layer **145** may separate the nanosheet stacked structure NSS and the gate electrode **150**.

(94) In the first region **R1**, the plurality of first source/drain regions **160Aa** may be formed on the plurality of first fin-type active areas FAA, and in the second region **R2**, the plurality of second source/drain regions **160B** may be formed on the plurality of second fin-type active areas FAB. Each of the plurality of first source/drain regions **160Aa** and the plurality of second source/drain regions **160B** may be connected to adjacent ends of the plurality of nanosheets **N1**, **N2**, and **N3**. In the first region **R1**, the plurality of first source/drain regions **160Aa** may fill a plurality of first recess regions **RS1a**, and extend into the SOI substrate layer **100A**. In some embodiments, in the first region **R1**, each of the plurality of first source/drain regions **160Aa** may penetrate the cover substrate layer **103**, but may not extend into the insulating substrate layer **102**, and the lower surface of each of the plurality of first source/drain regions **160Aa** may contact the insulating substrate layer **102**. In the first region **R1**, each of the plurality of first source/drain regions **160Aa** may not contact the first impurity region **104**. In the second region **R2**, the plurality of second source/drain region **160B** may fill the plurality of second recess region **RS2** and extend into the semiconductor substrate layer **100B**, and the lower surface of the plurality of second source/drain region **160B** may contact the lower surface of the second impurity region **105**. The lower surface of the first source/drain region **160Aa** may be at a first vertical level **LV1a**, and the lower surface of the second source/drain region **160B** may be at the second vertical level **LV2** that is higher than the first vertical level **LV1a**.

(95) The gate spacer **130** sequentially covering side walls of the gate electrode **150** may be formed on the plurality of nanosheet stacked structures NSS, the plurality of first fin-type active areas FAA, and the plurality of second fin-type active areas FAB.

(96) In the first region **R1**, the insulating spacer **140** that contacts the first source/drain region **160Aa** may be formed in the space between each of the plurality of nanosheets **N1**, **N2**, and **N3**. In the second region **R2**, the insulating spacer **140** may not be formed, and the second source/drain region **160B** may contact (e.g., directly contact) the gate dielectric layer **145**.

(97) The inter-gate insulating layer **172** and the inter-layer insulating layer **174** may be sequentially formed on the plurality of first source/drain regions **160Aa** and the plurality of second source/drain regions **160B**. The plurality of first contact plugs **192** may be connected to the plurality of first source/drain regions **160Aa** and the plurality of second source/drain regions **160B**. The plurality of

first contact plugs **192** may penetrate the inter-layer insulating layer **174** and the inter-gate insulating layer **172**, and may be connected to the plurality of first source/drain regions **160Aa** and the plurality of second source/drain regions **160B**. The metal silicide layer **162** may be arranged between the plurality of first source/drain regions **160Aa** and the plurality of second source/drain regions **160B**, and the first contact plug **192**.

(98) Referring to FIG. **17**, in the integrated circuit device **1b** illustrated in FIG. **16**, all of the lower surfaces of the plurality of first source/drain regions **160Aa** may contact the upper surface of the insulating substrate layer **102** on the lower surface of the first recess region **RS1a**, but an integrated circuit device **1c** as illustrated in FIG. **17** may include an air gap **AGa** arranged between each of the plurality of first source/drain regions **160Aa** and the insulating substrate layer **102**. For example, the air gap **AGa** may be arranged between each of the plurality of first source/drain region **160Aa** and the insulating substrate layer **102**, across the lower surface of a first recess region **RS1a**. Because the air gap **AGa** reduces parasite capacitance, the operation characteristic of the integrated circuit device **1c** may be improved.

(99) Referring to FIG. **18**, an integrated circuit device **1d** may include the plurality of first transistors **TRAb** equipped in the first region **R1**, and the plurality of second transistors **TRB** equipped in the second region **R2**. Each of the first transistor **TRAb** and the second transistor **TRB** may include the multi-gate MOSFET.

(100) The integrated circuit device **1d** may include a plurality of first source/drain regions **160Ab** and the plurality of second source/drain regions **160B**. In the first region **R1**, the plurality of first source/drain regions **160Ab** may be formed on the plurality of first fin-type active areas **FAA**, and in the second region **R2**, the plurality of second source/drain regions **160B** may be formed on the plurality of second fin-type active areas **FAB**. Each of the plurality of first source/drain regions **160Ab** and the plurality of second source/drain regions **160B** may be connected to adjacent ends of the plurality of nanosheets **N1**, **N2**, and **N3**. In the first region **R1**, the plurality of first source/drain regions **160Ab** may fill a plurality of first recess regions **RS1b**, and extend into the SOI substrate layer **100A**. In some embodiments, in the first region **R1**, each of the plurality of first source/drain regions **160Ab** may penetrate both the cover substrate layer **103** and the insulating substrate layer **102**, and extend into the first impurity region **104** of the base substrate layer **101**. A lower surface of each of the plurality of first source/drain regions **160Ab** may contact the base substrate layer **101**. In the first region **R1**, each of the plurality of first source/drain regions **160Ab** may contact the first impurity region **104**. In the second region **R2**, the plurality of second source/drain regions **160B** may fill the plurality of second recess regions **RS2** and extend into the semiconductor substrate layer **100B**, and the lower surface of the plurality of second source/drain regions **160B** may contact the lower surface of the second impurity region **105**. The lower surface of the first source/drain region **160Ab** may be at a first vertical level **LV1b**, and the lower surface of the second source/drain region **160B** may be at the second vertical level **LV2** that is higher than the first vertical level **LV1b**, or farther from the main surface **100M**.

(101) In the first region **R1**, the insulating spacer **140** contacting the first source/drain region **160Ab** may be formed in the space between each of the plurality of nanosheets **N1**, **N2**, and **N3**. In the second region **R2**, the insulating spacer **140** may not be formed, and the second source/drain region **160B** may contact (e.g., directly contact) the gate dielectric layer **145**.

(102) Referring to FIG. **19**, in the integrated circuit device **1d** illustrated in FIG. **18**, the plurality of first source/drain regions **160Ab** may contact all the side surfaces of the insulating substrate layer **102** on the side surfaces of the first recess region **RS1b**, but an integrated circuit device **1e** as illustrated in FIG. **19** may include an air gap **AGb** arranged between each of the plurality of first source/drain regions **160Ab** and the insulating substrate layer **102**. For example, the air gap **AGb** may be arranged between each of the plurality of first source/drain region **160Ab** and the insulating substrate layer **102**, on the sides of the first recess region **RS1b**. Because the air gap **AGb** reduces parasite capacitance, an operation characteristic of the integrated circuit device **1e** may be

improved.

(103) FIGS. **20A** and **20B** are cross-sectional views of integrated circuit devices, according to some embodiments. FIGS. **20A** and **20B** are cross-sectional views illustrating the X-Z surfaces.

(104) Referring to FIG. **20**, an integrated circuit device **2** may include the plurality of first transistors **TRA** equipped in the first region **R1**, and a plurality of third transistors **TRC** equipped in a third region **R3**. Each of the first transistor **TRA** and the third transistor **TRC** may include a multi-gate MOSFET. In some embodiments, the first transistor **TRA** equipped in the first region **R1** and the third transistor **TRC** equipped in the third region **R3** may include a multi-gate nMOSFET. In some embodiments, one of the first region **R1** and the third region **R3** may be an SRAM region, and the other may be a logic region.

(105) The integrated circuit device **2** may include the plurality of first fin-type active areas **FAA** and a plurality of third fin-type active areas **FAC** that protrude upward in the vertical direction (**Z** direction) from the main surface **100M** of the substrate including the SOI substrate layer **100A**, and the plurality of nanosheet stacked structures **NSS** that face the upper surfaces of the plurality of first fin-type active areas **FAA** and the plurality of third fin-type active areas **FAC** from locations spaced apart in the vertical direction (**Z** direction) from the upper surfaces of the plurality of first fin-type active areas **FAA** and the plurality of third fin-type active areas **FAC**.

(106) The plurality of nanosheet stacked structures **NSS** may be spaced apart from the upper surfaces of the plurality of first fin-type active areas **FAA** and the plurality of third fin-type active areas **FAC**. The plurality of nanosheet stacked structures **NSS** may include the plurality of nanosheets **N1**, **N2**, and **N3** that extend in parallel with the upper surfaces of the plurality of first fin-type active areas **FAA** and the plurality of third fin-type active areas **FAC** on the substrate including the SOI substrate layer **100A**.

(107) The plurality of gate electrodes **150** may extend in the second horizontal direction (**Y** direction) that crosses the first horizontal direction (**X** direction), and may extend on the plurality of first fin-type active areas **FAA** and the plurality of third fin-type active areas **FAC**. The gate electrode **150** may include the main gate unit **150M** that covers the upper surface of the nanosheet stacked structure **NSS**, and the plurality of sub-gate units **150S** that are connected to the main gate unit **150M** and formed in spaces between the plurality of first fin-type active areas **FAA** and the plurality of third fin-type active areas **FAC** and the plurality of nanosheets **N1**, **N2**, and **N3**, that is, under each of the plurality of nanosheets **N1**, **N2**, and **N3**. The gate dielectric layer **145** may separate the nanosheet stacked structure **NSS** and the gate electrode **150**.

(108) In the first region **R1**, the plurality of first source/drain regions **160A** may be formed on the plurality of first fin-type active areas **FAA**, and in the third region **R3**, the plurality of third source/drain regions **160C** may be formed on the plurality of third fin-type active areas **FAC**. In some embodiments, the plurality of first source/drain regions **160A** and the plurality of third source/drain regions **160C** may include the same material as each other. For example, the plurality of first source/drain regions **160A** and the plurality of third source/drain regions **160C** may include **Si**, but not **Ge**. Each of the plurality of first source/drain regions **160A** and the plurality of third source/drain regions **160C** may be connected to adjacent ends of the plurality of nanosheets **N1**, **N2**, and **N3**. In the first region **R1**, the plurality of first source/drain regions **160A** may fill a plurality of first recess regions **RS1**, and extend into the SOI substrate layer **100A**. In some embodiments, in the first region **R1**, each of the plurality of first source/drain regions **160A** may penetrate the cover substrate layer **103**, and extend into the insulating substrate layer **102**, and the lower surface of each of the plurality of first source/drain regions **160A** may contact the insulating substrate layer **102**. In the third region **R3**, the plurality of third source/drain regions **160C** may fill a plurality of third recess regions **RS3**, and extend into the SOI substrate layer **100A**. In some embodiments, in the third region **R3**, each of the plurality of third source/drain regions **160C** may penetrate the cover substrate layer **103**, and extend into the insulating substrate layer **102**, and the lower surface of each of the plurality of third source/drain regions **160C** may contact the insulating

substrate layer **102**. The lower surface of the first source/drain region **160A** may be at the first vertical level **LV1**, and the lower surface of the third source/drain region **160C** may be located at a third vertical level **LV3** higher than the first vertical level **LV1**, or farther from the main surface **100M**.

(109) The gate spacer **130** sequentially covering side walls of the gate electrode **150** may be formed on the plurality of nanosheet stacked structures **NSS**, the plurality of first fin-type active areas **FAA**, and the plurality of third fin-type active areas **FAC**.

(110) In the first region **R1**, the insulating spacer **140** that contacts the first source/drain region **160A** may be formed in a space between each of the plurality of nanosheets **N1**, **N2**, and **N3**, and in the third region **R3**, the insulating spacer **140** that contacts the third source/drain region **160C** may be formed in a space between each of the plurality of nanosheets **N1**, **N2**, and **N3**.

(111) The inter-gate insulating layer **172** and the inter-layer insulating layer **174** may be sequentially formed on the plurality of first source/drain regions **160Aa** and the plurality of third source/drain regions **160C**. The plurality of first contact plugs **192** may be connected to the plurality of first source/drain regions **160A** and the plurality of third source/drain regions **160C**. The plurality of first contact plugs **192** may penetrate the inter-layer insulating layer **174** and the inter-gate insulating layer **172**, and may be connected to the plurality of first source/drain regions **160A** and the plurality of third source/drain regions **160C**. The metal silicide layer **162** may be arranged between the plurality of first source/drain regions **160A** and the plurality of third source/drain regions **160C**, and the first contact plug **192**.

(112) Referring to FIG. **20b**, an integrated circuit device **2a** may include the plurality of first transistors **TRA** equipped in the first region **R1**, and a plurality of third transistors **TRCa** equipped in the third region **R3**. Each of the first transistor **TRA** and the third transistor **TRCa** may include a multi-gate MOSFET. In some embodiments, the first transistor **TRA** equipped in the first region **R1** and the third transistor **TRCa** equipped in the third region **R3** may include a multi-gate nMOSFET. In some embodiments, one of the first region **R1** and the third region **R3** may be an SRAM region, and the other may be a logic region.

(113) In the first region **R1**, the plurality of first source/drain regions **160A** may be formed on the plurality of first fin-type active areas **FAA**, and in the third region **R3**, the plurality of third source/drain regions **160Ca** may be formed on the plurality of third fin-type active areas **FAC**. In some embodiments, the plurality of first source/drain regions **160A** and the plurality of third source/drain regions **160Ca** may include the same material as each other. For example, the plurality of first source/drain regions **160A** and the plurality of third source/drain regions **160Ca** may include **Si**, but not **Ge**. Each of the plurality of first source/drain regions **160A** and the plurality of third source/drain regions **160Ca** may be connected to adjacent ends of the plurality of nanosheets **N1**, **N2**, and **N3**. In the first region **R1**, the plurality of first source/drain regions **160A** may fill a plurality of first recess regions **RS1**, and extend into the SOI substrate layer **100A**. In some embodiments, in the first region **R1**, each of the plurality of first source/drain regions **160A** may penetrate the cover substrate layer **103**, and extend into the insulating substrate layer **102**, and the lower surface of each of the plurality of first source/drain regions **160A** may contact the insulating substrate layer **102**. In the third region **R3**, the plurality of third source/drain regions **160Ca** may fill a plurality of third recess regions **RS3a**, and extend into the SOI substrate layer **100A**. In some embodiments, in the third region **R3**, each of the plurality of third source/drain regions **160Ca** may penetrate the cover substrate layer **103** and the insulating substrate layer **102**, and extend into the first impurity region **104** of the base substrate layer **101**, and a lower surface of each of the plurality of third source/drain regions **160Ca** may contact a first impurity region **102**. The lower surface of the first source/drain region **160A** may be at the first vertical level **LV1**, and the lower surface of the third source/drain region **160Ca** may be located at a third vertical level **LV3a** lower than the first vertical level **LV1**, or closer to the main surface **100M**.

(114) FIG. **21** is a cross-sectional view of an integrated circuit device, according to an embodiment.

FIG. 21 is a cross-sectional view illustrating the X-Z surface.

(115) Referring to FIG. 21, an integrated circuit device 3 may include the plurality of first transistors TRA equipped in the first region R1, and a plurality of four transistors TRD equipped in a fourth region R4. Each of the first transistor TRA and the fourth transistor TRD may include a multi-gate MOSFET. In some embodiments, the first transistor TRA equipped in the first region R1 and the fourth transistor TRD equipped in the fourth region R4 may include a multi-gate nMOSFET. In some embodiments, one of the first region R1 and the fourth region R4 may be an SRAM region, and the other may be a logic region.

(116) The integrated circuit device 3 may include the plurality of first fin-type active areas FAA and the plurality of fourth fin-type active areas FAD that protrude upward in the vertical direction (Z direction) from the main surface 100M of the substrate including the SOI substrate layer 100A and the semiconductor substrate layer 100B, and the plurality of nanosheet stacked structures NSS that face upper surfaces of the plurality of first fin-type active areas FAA and the plurality of fourth fin-type active areas FAD from locations spaced apart from the plurality of first fin-type active areas FAA and the plurality of fourth fin-type active areas FAD. The plurality of first fin-type active areas FAA may protrude upward in the vertical direction (Z direction) from the main surface 100M of the SOI substrate layer 100A in the first region R1, and the plurality of fourth fin-type active areas FAD may protrude upward in the vertical direction (Z direction) from the main surface 100M of the semiconductor substrate layer 100B in the fourth region R4.

(117) Instead of the second impurity region 105 formed on the semiconductor substrate layer 100B in the second region R2 of the integrated circuit device 1 illustrated in FIGS. 14A and 14B, the integrated circuit device 4 may include a third impurity region 104a formed on the semiconductor substrate layer 100B in the fourth region R4. The first impurity region 104 may be formed by injecting impurity of a first conductivity into a portion of the SOI substrate layer 100A, and the third impurity region 104a may be formed by injecting impurity of a first conductivity into a portion of the semiconductor substrate layer 100B. In some embodiments, a shape of the third impurity region 104a may be substantially the same as a shape of the second impurity region 105 illustrated in FIGS. 14A and 14B.

(118) The plurality of nanosheet stacked structures NSS may be spaced apart from the upper surfaces of the plurality of first fin-type active areas FAA and the plurality of fourth fin-type active areas FAD. The plurality of nanosheet stacked structures NSS may include the plurality of nanosheets N1, N2, and N3 that extend in parallel with the upper surfaces of the plurality of first fin-type active areas FAA and the plurality of fourth fin-type active areas FAD on the substrate including the SOI substrate layer 100A and the semiconductor substrate layer 100B. The plurality of nanosheets N1, N2, and N3 of one nanosheet stacked structure NSS may be sequentially stacked one-by-one on the upper surfaces of the plurality of first fin-type active areas FAA and the plurality of fourth fin-type active areas FAD.

(119) The plurality of gate electrodes 150 may extend in the second horizontal direction (Y direction) that cross the first horizontal direction (X direction), and may extend on the plurality of first fin-type active areas FAA and the plurality of fourth fin-type active areas FAD. Each of the plurality of gate electrodes 150 may cover the nanosheet stacked structure NSS, and surround at least a portion of the plurality of nanosheet stacked structures NSS. The gate electrode 150 may include the main gate unit 150M that covers the upper surface of the nanosheet stacked structure NSS, and the plurality of sub-gate units 150S that are connected to the main gate unit 150M and formed in spaces between the plurality of first fin-type active areas FAA and the plurality of fourth fin-type active areas FAD and the plurality of nanosheets N1, N2, and N3, that is, under each of the plurality of nanosheets N1, N2, and N3. The gate dielectric layer 145 may separate the nanosheet stacked structure NSS and the gate electrode 150.

(120) In the first region R1, the plurality of first source/drain regions 160A may be formed on the plurality of first fin-type active areas FAA, and in the fourth region R4, the plurality of fourth

source/drain regions **160D** may be formed on the plurality of fourth fin-type active areas **FAD**. Each of the plurality of first source/drain regions **160A** and the plurality of fourth source/drain regions **160D** may be connected to adjacent ends of the plurality of nanosheets **N1**, **N2**, and **N3**. In some embodiments, the plurality of first source/drain regions **160A** and the plurality of fourth source/drain regions **160D** may include the same material as each other.

(121) In the first region **R1**, each of the plurality of first source/drain regions **160A** may extend into the SOI substrate layer **100A**. In some embodiments, in the first region **R1**, each of the plurality of first source/drain regions **160A** may penetrate the cover substrate layer **103**, and extend into the insulating substrate layer **102**, and the lower surface of each of the plurality of first source/drain regions **160A** may contact the insulating substrate layer **102**. In the fourth region **R4**, each of the plurality of fourth source/drain regions **160D** may extend into the semiconductor substrate layer **100B**, and a lower surface of each of the plurality of fourth source/drain regions **160D** may contact the third impurity region **104a**. The lower surface of the first source/drain region **160A** may be at the first vertical level **LV1**, and the lower surface of the fourth source/drain region **160D** may be located at a fourth vertical level **LV4** higher than the first vertical level **LV1** or farther from the main surface **100M**.

(122) The gate spacer **130** sequentially covering side walls of the gate electrode **150** may be formed on the plurality of nanosheet stacked structures **NSS**, the plurality of first fin-type active areas **FAA**, and the plurality of fourth fin-type active areas **FAD**.

(123) In the first region **R1**, the insulating spacer **140** that contacts the first source/drain region **160A** may be formed in a space between each of the plurality of nanosheets **N1**, **N2**, and **N3**, and in the fourth region **R4**, the insulating spacer **140** that contacts the fourth source/drain region **160D** may be formed in a space between each of the plurality of nanosheets **N1**, **N2**, and **N3**.

(124) The inter-gate insulating layer **172** and the inter-layer insulating layer **174** may be sequentially formed on the plurality of first source/drain regions **160A** and the plurality of fourth source/drain regions **160D**. Each of the inter-gate insulating layer **172** and the inter-layer insulating layer **174** may include a silicon oxide layer, but the present disclosure is not limited thereto.

(125) The plurality of first contact plugs **192** may be connected to the plurality of first source/drain regions **160A** and the plurality of fourth source/drain regions **160D**. The plurality of first contact plugs **192** may penetrate the inter-layer insulating layer **174** and the inter-gate insulating layer **172**, and may be connected to the plurality of first source/drain regions **160A** and the plurality of fourth source/drain regions **160D**. The metal silicide layer **162** may be arranged between the plurality of first source/drain regions **160A** and the plurality of fourth source/drain regions **160D**, and the first contact plug **192**.

(126) FIGS. **22A** through **23B** are cross-sectional views illustrating a manufacturing method of an integrated circuit device, and describing the integrated circuit device manufactured by using the manufacturing method according to manufacturing sequences, according to some embodiments. FIGS. **22A** through **23A** are cross-sectional views illustrating a Y-Z surface, and FIG. **23B** is a cross-sectional view illustrating the Y-Z surface taken along **V1-V1'** and **V5-V5'** lines in FIG. **23A**.

(127) Referring to FIG. **22A**, a stacked structure of alternately arranged ones of a plurality of sacrificial semiconductor layers **106S** and one of a plurality of nanosheet semiconductor layers **NS** may be formed on a substrate including the first region **R1** in which the SOI substrate layer **100A** is arranged and a fifth region **R5** in which the semiconductor substrate layer **100B** is arranged. A stack recess **SR** may be formed by removing a portion of the stacked structure of the plurality of sacrificial semiconductor layers **106S** and the plurality of nanosheet semiconductor layers **NS** formed in the fifth region **R5**. As a result, the upper surface of the semiconductor substrate layer **100B** may be exposed in the fifth region **R5**. In some embodiments, the semiconductor substrate layer **100B** in the fifth region **R5** may be substantially the same as the semiconductor substrate layer **100B** in the second region **R2** illustrated in FIG. **5**.

(128) Referring to FIG. **22B**, a semiconductor epi-layer **110** may be formed on the semiconductor

substrate layer **100B** in the fifth region **R5**. The semiconductor epi-layer **110** may include a semiconductor material. The semiconductor epi-layer **110** may be formed to have the same crystallization as the semiconductor substrate layer **100B**. In some embodiments, the semiconductor epi-layer **110** may include a semiconductor material of the same type as the semiconductor substrate layer **100B**. In some embodiments, the semiconductor epi-layer **110** may include a different type of semiconductor material having the same crystallization as the semiconductor substrate layer **100B**.

(129) The semiconductor epi-layer **110** may be formed with an impurity of the same conductivity as the second impurity region **105**. For example, the impurity of a second conductivity may be injected into the semiconductor epi-layer **110**.

(130) In some embodiments, in the fifth region **R5**, similarly to the first region **R1** in FIG. 5, a structure similar to that illustrated in FIG. 22B may be formed, by stacking alternately ones of the plurality of sacrificial semiconductor layers **106S** and ones of the plurality of nanosheet semiconductor layers **NS** on the SOI substrate layer **100A**, then removing all of a portion formed in a stacked structure of the plurality of sacrificial semiconductor layers **106S** and the plurality of nanosheet semiconductor layers **NS** in the fifth region **R5**, and also a portion of the cover substrate layer **103** and the insulating substrate layer **102** in the fifth region **R5**, and then forming an epi-layer corresponding to the second impurity region **105** and the semiconductor epi-layer **110** in the epitaxial growth method.

(131) Referring to FIGS. 23A and 23B together, the integrated circuit device **4** may be formed by performing processes similar to those described with reference to FIGS. 6 through 14B on a result of FIG. 22B. The integrated circuit device **4** may include the plurality of first fin-type active areas **FAA** and the plurality of fifth fin-type active areas **FAE** that protrude upward in the vertical direction (**Z** direction) from the main surface **100M** of the substrate including the SOI substrate layer **100A** and the semiconductor substrate layer **100B**, and the plurality of nanosheet stacked structures **NSS** that face the upper surfaces of the plurality of first fin-type active areas **FAA** from locations spaced apart from the upper surfaces of the plurality of first fin-type active areas **FAA** in the first region **R1**. The plurality of first fin-type active areas **FAA** may protrude upward in the vertical direction (**Z** direction) from the main surface **100M** of the SOI substrate layer **100A** in the first region **R1**, and the plurality of fifth fin-type active areas **FAE** may protrude upward in the vertical direction (**Z** direction) from the main surface **100M** of the semiconductor substrate layer **100B** in the fifth region **R5**.

(132) The plurality of trenches **TRE** may limit or define the plurality of first fin-type active areas **FAA** and the plurality of fifth fin-type active areas **FAE** on the substrate including the SOI substrate layer **100A** and the semiconductor substrate layer **100B**. Side walls of the plurality of first fin-type active areas **FAA** and the plurality of fifth fin-type active areas **FAE** may be covered by a device separating layer **118** that fills the plurality of trenches **TRE**. Levels of the upper surfaces of the plurality of first fin-type active areas **FAA**, a level of an upper surface of the second impurity region **105** of the plurality of fifth fin-type active areas **FAE**, and a level of an upper surface of the device separating layer **118** from the main surface **100M** may be equal, the same as, or similar to each other.

(133) The plurality of nanosheet stacked structures **NSS** may be spaced apart from the upper surfaces of the plurality of first fin-type active areas **FAA**. The plurality of nanosheet stacked structures **NSS** may include the plurality of nanosheets **N1**, **N2**, and **N3** extending in parallel with the upper surfaces of the plurality of first fin-type active areas **FAA** on the SOI substrate layer **100A**. The plurality of nanosheets **N1**, **N2**, and **N3** of one nanosheet stacked structure **NSS** may be sequentially stacked one-by-one on the upper surfaces of the plurality of first fin-type active areas **FAA**.

(134) The nanosheet stacked structure **NSS** of the plurality of nanosheets **N1**, **N2**, and **N3** may be arranged on the plurality of first fin-type active areas **FAA** in the first region **R1**, and may be

located substantially at the same level as the semiconductor epi-layer **110** of each of the plurality of fifth fin-type active areas FAE in the fifth region **R5**. In other words, the nanosheet stacked structure NSS of the plurality of nanosheets **N1**, **N2**, and **N3** may be arranged on the plurality of first fin-type active areas FAA in the first region **R1** to be located substantially at the same level as upper portions of the plurality of fifth fin-type active areas FAE in the fifth region **R5** from the main surface **100M**.

(135) The plurality of gate electrodes **150** may extend in the second horizontal direction (Y direction) that crosses the first horizontal direction (X direction), and may extend on the plurality of first fin-type active areas FAA and the plurality of fifth fin-type active areas FAE. At least some of the plurality of gate electrodes **150** may overlap in the vertical direction (Z direction) each of the plurality of nanosheet stacked structures NSS in the first region **R1**, and may also overlap in the vertical direction (Z direction) the plurality of fifth fin-type active areas FAE in a periphery circuit region PR.

(136) In the first region **R1**, each of the plurality of gate electrodes **150** may cover the nanosheet stacked structure NSS, and surround at least a portion of the plurality of nanosheet stacked structures NSS. In the first region **R1**, the gate electrode **150** may include the main gate unit **150M** that covers the upper surface of the nanosheet stacked structure NSS, and the plurality of sub-gate units **150S** that are connected to the main gate unit **150M** and formed in spaces between the first fin-type active area FAA and the plurality of nanosheets **N1**, **N2**, and **N3**, that is, under each of the plurality of nanosheets **N1**, **N2**, and **N3**. The gate dielectric layer **145** may separate the nanosheet stacked structure NSS and the gate electrode **150**.

(137) In the fifth region **R5**, the plurality of gate electrodes **150** may cover surfaces of the plurality of fifth fin-type active areas FAE. In the fifth region **R5**, the plurality of gate electrodes **150** may include only the main gate unit **150M**, and may not include the sub-gate unit **150S**. The gate dielectric layer **145** may separate the fifth fin-type active area FAE and the gate electrode **150**.

(138) In the first region **R1**, the plurality of first source/drain regions **160A** may be formed on the plurality of first fin-type active areas FAA. In the first region **R1**, each of the plurality of first source/drain regions **160A** may be connected to adjacent ends of the plurality of nanosheets **N1**, **N2**, and **N3**. In the fifth region **R5**, a plurality of fifth source/drain regions **160E** may be connected to side walls of fifth fin-type active area FAE adjacent to each other of the plurality of fifth fin-type active areas FAE. In the first region **R1**, each of the plurality of first source/drain regions **160A** may extend into the SOI substrate layer **100A**. In some embodiments, in the first region **R1**, each of the plurality of first source/drain regions **160A** may penetrate the cover substrate layer **103**, and extend into the insulating substrate layer **102**, and the lower surface of each of the plurality of first source/drain regions **160A** may contact the insulating substrate layer **102**. In the fifth region **R5**, each of the plurality of fifth source/drain regions **160E** may extend into the semiconductor substrate layer **100B**, and the lower surface of each of the plurality of fifth source/drain regions **160E** may contact the second impurity region **105**. The lower surface of the first source/drain region **160A** may be at the first vertical level **LV1**, and the lower surface of the fifth source/drain region **160E** may be located at a fifth vertical level **LV5** higher than the first vertical level **LV1** or farther from the main surface **100M**.

(139) The integrated circuit device **4** may include a plurality of first transistors TRA equipped in the first region **R1**, and a plurality of fifth transistors TRS equipped in the fifth region **R5**. The first transistor TRA may include a multi-gate MOSFET, and the fifth transistor TRS may include a single-gate MOSFET. In some embodiments, the first transistor TRA equipped in the first region **R1** may include a multi-gate nMOSFET, and the fifth transistor TRS equipped in the fifth region **R5** may include a multi-gate pMOSFET. In some other embodiments, the first transistor TRA equipped in the first region **R1** may include a multi-gate nMOSFET, and the fifth transistor TRS equipped in the fifth region **R5** may include a multi-gate nMOSFET.

(140) The gate spacer **130** sequentially covering the side walls of the gate electrode **150** may be

formed on the plurality of nanosheet stacked structures NSS and the plurality of fifth fin-type active areas FAE. In the first region R1, the insulating spacer 140 that contacts the first source/drain region 160A may be formed in the space between each of the plurality of nanosheets N1, N2, and N3.

(141) The inter-gate insulating layer 172 and the inter-layer insulating layer 174 may be sequentially formed on the plurality of first source/drain regions 160A and the plurality of fifth source/drain regions 160E.

(142) The plurality of first contact plugs 192 may be connected to the plurality of first source/drain regions 160A and the plurality of fifth source/drain regions 160E. The plurality of first contact plugs 192 may penetrate the inter-layer insulating layer 174 and the inter-gate insulating layer 172, and may be connected to the plurality of first source/drain regions 160A and the plurality of fifth source/drain regions 160E. The metal silicide layer 162 may be arranged between the plurality of first source/drain regions 160A and the plurality of fifth source/drain regions 160E, and the first contact plug 192.

(143) The plurality of second contact plugs 194 may be connected to the plurality of gate electrodes 150. The second contact plug 194 may penetrate an inter-layer insulating layer 174, and be connected to the gate electrode 150.

(144) In some embodiments of the present disclosure, integrated circuit devices may include at least two regions of a first region R1, a second region R2, a third region R3, a fourth region R4, and/or a fifth region R5, which are illustrated in FIGS. 1-23B and described with reference to integrated circuit devices 1, 1a, 1b, 1c, 1d, 1e, 2, 2a, 3, and 4. Such embodiments should be easily understood by those skilled in the art in view of the above discussion, and thus, will not be separately illustrated.

(145) In addition, among components commonly arranged in at least two regions of the first region R1, the second region R2, the third region R3, the fourth region R4, and the fifth region R5, components arranged in different regions from each other may be respectively and differently referred to as a first, a second, etc. For example, nanosheet stacked structures NSS including a plurality of nanosheets N1, N2, and N3 arranged in the first region R1 and the second region R2 may be referred to as a first nanosheet stacked structure including a plurality of first nanosheets, and a second nanosheet structure including a plurality of second nanosheets, respectively.

(146) While the inventive concepts have been particularly shown and described with reference to examples of embodiments thereof, it will be understood that various changes in form and details may be made therein without departing from the scope of the following claims.

Claims

1. A method of manufacturing an integrated circuit device, the method comprising: preparing a semiconductor on insulator (SOI) substrate layer having a first region and a second region, the SOI substrate including a base substrate layer, an insulating substrate layer on the base substrate layer, and a cover substrate layer on the insulating substrate layer; forming a substrate recess by removing the cover substrate layer and the insulating substrate layer in the second region; forming an epi-substrate layer within the substrate recess in the second region, the epi-substrate layer and a portion of the base substrate layer in the second region constituting a semiconductor substrate layer; forming a stacked structure of a plurality of sacrificial semiconductor layers and a plurality of nanosheet semiconductor layers on the SOI substrate layer and the semiconductor substrate layer, the plurality of sacrificial semiconductor layers and the plurality of nanosheet semiconductor layers being alternately stacked on the SOI substrate layer and the semiconductor substrate layer; forming a plurality of first fin-type active areas in the first region, a plurality of second fin-type active areas in the second region, and a plurality of nanosheet stacked structures above the plurality of first fin-type active areas and the plurality of second fin-type active areas, by etching the stacked structure

of the plurality of sacrificial semiconductor layers and the plurality of nanosheet semiconductor layers, portions of the SOI substrate layer, and portions of the semiconductor substrate layer, wherein each of the plurality of nanosheet stacked structures comprising a plurality of nanosheets; forming a plurality of first source/drain regions between adjacent nanosheet stacked structures in the first region; and forming a plurality of second source/drain regions between adjacent nanosheet stacked structures in the second region.

2. The method of claim 1, wherein each of the plurality of first source/drain regions extends into the SOI substrate layer, is in contact with the insulating substrate layer, and has a lower surface at a first vertical level.

3. The method of claim 2, wherein each of the plurality of second source/drain regions extends into the semiconductor substrate layer and has a lower surface at a second vertical level that is farther from a main surface of the SOI substrate layer and a surface of the semiconductor substrate layer than the first vertical level.

4. The method of claim 1, wherein each of the plurality of first source/drain regions extends through the cover substrate layer and into the insulating substrate layer.

5. The method of claim 1, wherein each of the plurality of first source/drain regions extends through the cover substrate layer and contacts the insulating substrate layer without extending into the insulating substrate layer.

6. The method of claim 1, wherein each of the plurality of first source/drain regions extends through the cover substrate layer and the insulating substrate layer, and wherein each of the plurality of first source/drain regions contacts the base substrate layer.

7. The method of claim 1, further comprising: forming a plurality of gate electrodes extending on the plurality of first fin-type active areas and the plurality of second fin-type active areas, each of the plurality of gate electrodes comprising a main gate unit above a respective one of the plurality of nanosheet stacked structures and a plurality of sub-gate units underneath each of the plurality of nanosheets of the respective one of the plurality of nanosheet stacked structures.

8. The method of claim 7, further comprising: forming a gate dielectric layer separating the plurality of gate electrodes and plurality of nanosheet stacked structures.

9. The method of claim 8, further comprising: forming a plurality of insulating spacers in the first region, the plurality of insulating spacers between the plurality of first source/drain regions and the plurality of nanosheets, the plurality of insulating spacers covering first and second ends of the plurality of sub-gate units with the gate dielectric layer therebetween.

10. The method of claim 9, wherein, in the second region, the gate dielectric layer is arranged between the plurality of sub-gate units and the plurality of second source/drain regions, and wherein the gate dielectric layer directly contacts the plurality of sub-gate units and the plurality of second source/drain regions.

11. A method of manufacturing an integrated circuit device, the method comprising: preparing a semiconductor on insulator (SOI) substrate layer having a first region and a second region, the SOI substrate including a base substrate layer, an insulating substrate layer on the base substrate layer, and a cover substrate layer on the insulating substrate layer; forming a substrate recess by removing the cover substrate layer, the insulating substrate layer, and an upper portion of the base substrate layer in the second region; forming an epi-substrate layer within the substrate recess in the second region, the epi-substrate layer and portion of the base substrate layer in the second region constituting a semiconductor substrate layer; forming a first impurity region by injecting an impurity of a first conductivity into a portion of the SOI substrate layer in the first region; forming a second impurity region by injecting an impurity of a second conductivity into a portion of the semiconductor substrate layer in the second region; forming a stacked structure of a plurality of sacrificial semiconductor layers and a plurality of nanosheet semiconductor layers on the SOI substrate layer and the semiconductor substrate layer, the plurality of sacrificial semiconductor layers and the plurality of nanosheet semiconductor layers being alternately stacked on the SOI

substrate layer and the semiconductor substrate layer; forming a plurality of first fin-type active areas in the first region, a plurality of second fin-type active areas in the second region, and a plurality of nanosheet stacked structures above the plurality of first fin-type active areas and the plurality of second fin-type active areas, by etching the stacked structure of the plurality of sacrificial semiconductor layers and the plurality of nanosheet semiconductor layers, portions of the SOI substrate layer, and portions of the semiconductor substrate layer, each of the plurality of nanosheet stacked structures comprising a plurality of nanosheets; forming a plurality of first recess regions in the first region and a plurality of second recess regions in the second region by removing portions of the plurality of nanosheet stacked structures and portions of the plurality of sacrificial semiconductor layers; and forming a plurality of first source/drain regions within the plurality of first recess regions and a plurality of second source/drain regions within the plurality of second recess regions.

12. The method of claim 11, wherein a bottom of each of the plurality of first recess regions is at a first vertical level, and wherein a bottom of each of the plurality of second recess regions is at a second vertical level different from the first vertical level.

13. The method of claim 12, wherein each of the plurality of first source/drain regions extends into the SOI substrate layer and is in contact with the insulating substrate layer and has a lower surface at the first vertical level, and wherein each of the plurality of second source/drain regions extends into the semiconductor substrate layer and has a lower surface at the second vertical level.

14. The method of claim 11, further comprising: removing portions of the plurality of sacrificial semiconductor layers exposed to both sides of each of the plurality of nanosheet stacked structures in the plurality of first recess regions in the first region; and forming a plurality of insulating spacers that are in areas between each of the plurality of nanosheets in the first region.

15. The method of claim 14, further comprising: forming a gate dielectric layer and a plurality of gate electrodes, wherein the plurality of gate electrodes extends on the plurality of first fin-type active areas and the plurality of second fin-type active areas, wherein each of the plurality of gate electrodes comprises a main gate unit above a respective one of the plurality of nanosheet stacked structures and a plurality of sub-gate units underneath each of the plurality of nanosheets of the respective one of the plurality of nanosheet stacked structures, and wherein the gate dielectric layer separates the plurality of gate electrodes and the plurality of nanosheet stacked structures.

16. The method of claim 15, wherein the plurality of insulating spacers are arranged between the plurality of first source/drain regions and the plurality of nanosheets, and wherein the plurality of insulating spacers cover first and second ends of the plurality of sub-gate units with the gate dielectric layer therebetween.

17. The method of claim 11, wherein injecting the impurity of the first conductivity into a portion of the SOI substrate layer in the first region comprises injecting a p-type impurity; and wherein injecting the impurity of the second conductivity into a portion of the semiconductor substrate layer in the second region comprises injecting a n-type impurity.

18. The method of claim 11, wherein the first impurity region is arranged in a portion of an upper side of the base substrate layer, and wherein the plurality of first source/drain regions are free from contact with the first impurity region.

19. The method of claim 11, wherein the first impurity region is arranged in a portion of an upper side of the base substrate layer, and wherein the plurality of first source/drain regions contact the first impurity region.

20. The method of claim 11, wherein the insulating substrate layer has a thickness of about 10 nanometers (nm) to about 20 nm, wherein lower surfaces of the plurality of first source/drain regions contact the insulating substrate layer, and wherein the first impurity region is not in contact with the lower surfaces of the plurality of first source/drain regions.
